APPARATUS AND METHOD FOR SURFACE TREATMENT IN A FURNACE

ABSTRACT

The present invention relates apparatus and methods for treating the surfaces of substrates in a furnace to enhance the subsequent deposition of thin films or to enhance the reaction of the surfaces with gas phase components. Exhaust systems and methods of their use allow the exhaust gases to be conveyed to proper gas treatments facilities. Door seal and inert gas purge systems allow the furnace to be operated safely and minimize the reaction of the process gases in the door seal region.

Figure 1